

A B S T R A C T

This invention is a vacuum processing apparatus comprising of a vacuum processing area (14) having a stage (16) on which a substrate to be processed (17) is mounted, and a carrier port (18) provided on a peripheral wall of a processing chamber (11) forming the vacuum processing area (14) and carrying the substrate (17) onto and off the stage (16), for generating plasma in the vacuum processing area (14) and subjecting the substrate (17) on the stage (16) to a plasma processing, wherein a shutter (20) closing the carrier port (18) to prevent the plasma from being disordered when the plasma is generated in the vacuum processing chamber is provided.

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